

Special Issue

Surface Deposition and Nano-Film Fabrication Process

Message from the Guest Editors

Coating technologies have been developing for many decades, leading to the emergence of nano-films and enabling their application in many areas, such as optics, electronics, automotive, and many others. Depending on the required functionality of the material, various deposition methods can be used to obtain thin films and multilayer systems.

This Special Issue, “Surface Deposition and Nano-Film Fabrication Process”, is open for works that report the newest advances in the area of fabrication processes of thin and ultrathin films, including 2D and layered systems. The topics within the scope of the issue are, but are not limited to, the following: Optimization and controlling of MBE, PLD, CVD, ALD and sputtering techniques; Fabrication of electrical, optical, magnetic and other functional thin and ultrathin films, including 2D and layered systems; Study of materials' properties and advanced characterization; Applications of new nano-films and multilayered systems.

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